

REMARKS

This Amendment is being filed in response to the Office Action mailed July 9, 2008, which has been reviewed and carefully considered. Reconsideration and allowance of the present application in view of the amendments made above and the remarks to follow are respectfully requested.

In the Office Action, claims 1 and 4-8 are rejected under 35 U.S.C. §103(a) as allegedly unpatentable over U.S. Patent Application Publication No. 2003/0137065 (Medower) in view of U.S. Patent Application Publication No. 2003/0235388 (Lee). Further, claims 2 and 9-10 are rejected under 35 U.S.C. §103(a) as allegedly unpatentable over Medower in view Lee and U.S. Patent No. 6,872,511 (Hirokane). It is respectfully submitted that claims 1-2 and 4-11 are patentable Medower, Lee and Hirokane for at least the following reasons.

Medower is directed to use of a mother stamper for optical disk molding. As shown in FIG 1, and described in paragraph [0036], a glass master disk (also referred to as a "master") 100 is coated with a film 102 to improve adhesion for a deposited layer of

photoresist 104. The film 102 can be chrome, a saline coupling agent, or other suitable film.

As correctly noted on page 3 of the Office Action, Medower does not disclose or suggest rinsing and drying the photoresist layer thereby interrupting the dissolving act. It is alleged that drying after rinsing is well known.

It is respectfully submitted that assuming, arguendo, that drying after rinsing is well known, the present invention, as recited in independent claim 1, does not requires merely rinsing and drying. Rather, independent claim 1 specifically recites "rinsing and drying the photoresist layer thereby interrupting said dissolving act." (Illustrative emphasis provided) Interrupting the dissolving act is nowhere disclosed or suggested in Medower.

Further, as correctly noted on page 3 of the Office Action, Medower does not disclose or suggest that the metallic surface comprises Ni or Au. Lee is cited in an attempt to remedy the deficiencies in Medower.

Lee is directed to a method for fabricating an optical fiber block for optical coupling between an optical fiber and optical devices. The Lee optical fiber block is capable of preventing

degradations due to an outgassing from an epoxy material. As specifically recited in paragraph [0023], a "lower silicon substrate 10 is coated with a photoresist, and then, a surface of the lower silicon substrate 10 on which a solder 12 is set is exposed through an photolithography process. Thereafter, an adhesion layer 14 and a solder 12 are deposited on the exposed surface of the lower silicon substrate 10." (Emphasis added) The Lee adhesion layer 14 comprises multi layers of Ti/Ni/Au. Thus, the Lee adhesion layer 14 is formed ON the photoresist. Accordingly, the combination of Medower and Lee merely discloses or suggests having a glass master disk coated with a chrome film 102, a photoresist 104 deposited on the chrome film 102, and an adhesion layer of Ti/Ni/Au (14 of Lee) deposited ON the photoresist 104.

In stark contrast, the present invention as recited in independent claim 1, amongst other patentable elements recites (illustrative emphasis provided):

forming a metallic surface on a substrate.  
applying a photoresist layer, with a  
substantially uniform thickness, on the metallic  
surface, ...  
wherein the metallic surface comprises Ni or Au.

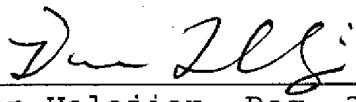
A metallic surface comprising Ni or Au formed on a substrate, where a photoresist layer is applied on the metallic surface, is nowhere disclosed or suggested in Medower, Lee, and combination thereof. Rather, the combination of Medower and Lee discloses an adhesion layer of Ti/Ni/Au deposited ON the photoresist. Hirokane is cited to allegedly show other features and does not remedy the deficiencies in Medower and Lee.

Accordingly, it is respectfully submitted that independent claim 1 are allowable, and allowance thereof is respectfully requested. In addition, it is respectfully submitted that claims 2 and 4-11 should also be allowed at least based on their dependence from amended independent claim 1.

In addition, Applicants deny any statement, position or averment of the Examiner that is not specifically addressed by the foregoing argument and response. Any rejections and/or points of argument not addressed would appear to be moot in view of the presented remarks. However, the Applicants reserve the right to submit further arguments in support of the above stated position, should that become necessary. No arguments are waived and none of the Examiner's statements are conceded.

In view of the above, it is respectfully submitted that the present application is in condition for allowance, and a Notice of Allowance is earnestly solicited.

Respectfully submitted,

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October 6, 2008

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